

L Number	Hits	Search Text	DB	Time stamp
1	1547	(427/552,553,555,558).CCLS.	USPAT; US-PGPUB	2004/08/16 09:26
2	1093	(427/226).CCLS.	USPAT; US-PGPUB	2004/08/16 09:26
3	2172	(427/248.1,255.18,255.23).CCLS.	USPAT; US-PGPUB	2004/08/16 09:26
4	3565	(427/256,259,270,271,272,282).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
5	552	(117/88,95).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
6	271	(438/503,507).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
7	245	(423/349).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
8	1161	(118/726).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
9	10032	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.)	USPAT; US-PGPUB	2004/08/16 09:27
10	3	((427/552,553,555,558).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:35
11	0	((427/226).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:32
12	10	((427/248.1,255.18,255.23).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:33

13	0	((427/256,259,270,271,272,282).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:33
14	1	((117/88,95).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:33
15	0	((438/503,507).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:33
16	0	((423/349).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:34
17	0	((423/349).CCLS.) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:34

18	0	((118/726).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:34
19	0	((118/726).CCLS.) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 09:34
20	14	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16-10:19

21	0	<p>((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not ((((427/552,553,555,558).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) or (((427/248.1,255.18,255.23).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) or (((117/88,95).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane)))</p>	USPAT; US-PGPUB	2004/08/16 09:35
22	41	<p>((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))</p>	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:43

23	8	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively)	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:44
24	33	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively))	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:39
25	168	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively))	USPAT; US-PGPUB	2004/08/16 09:43
26	133	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively))	USPAT; US-PGPUB	2004/08/16 09:44

27	133	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively or photomask\$3)	USPAT; US-PGPUB	2004/08/16 09:55
28	35	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) not (((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or selectively or photomask\$3))	USPAT; US-PGPUB	2004/08/16 09:58
29	2	((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.)) and (active with inactive with (\$4CVD or (vapor adj deposit\$3)))	USPAT; US-PGPUB	2004/08/16 09:59
30	15	(active with inactive with (\$4CVD or (vapor adj deposit\$3)))	USPAT; US-PGPUB	2004/08/16 10:00
31	13	((active with inactive with (\$4CVD or (vapor adj deposit\$3)))) not (((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.)) and (active with inactive with (\$4CVD or (vapor adj deposit\$3)))	USPAT; US-PGPUB US-PGPUB	2004/08/16 09:59
32	11	(active with inactive with (\$4CVD or (vapor adj deposit\$3)))	EPO; JPO; DERWENT; IBM TDB	2004/08/16 10:01

33	147	((118/726).CCLS.) and ((crucible or evaporator or source or substrate or liquid or solution) near7 (pattern\$3 or mask\$3 or SAM or photomask\$3 or monolayer or ((mono or molecular) near2 (layer or film)) or (self adj assembl\$3)))	USPAT; US-PGPUB	2004/08/16 10:17
34	25898	((Si or silicon or polysilicon) near4 (coat\$3 or deposit\$3 or film or layer or grow\$3 or \$4CVD) with (\$4CVD or (vapor adj deposit\$3)) same (selective\$3 or pattern\$3 or portion)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:23
35	253	((((Si or silicon or polysilicon) near4 (coat\$3 or deposit\$3 or film or layer or grow\$3 or \$4CVD) with (\$4CVD or (vapor adj deposit\$3)) same (selective\$3 or pattern\$3 or portion))) and ((427/552,553,555,558).CCLS.) ((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.) ((427/256,259,270,271,272,282).CCLS.) ((117/88,95).CCLS.) ((438/503,507).CCLS.) ((423/349).CCLS.) ((118/726).CCLS.))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:19
36	18	((((Si or silicon or polysilicon) near4 (coat\$3 or deposit\$3 or film or layer or grow\$3 or \$4CVD) with (\$4CVD or (vapor adj deposit\$3)) same (selective\$3 or pattern\$3 or portion))) and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))	USPAT; US-PGPUB	2004/08/16 10:20
37	21	((((Si or silicon or polysilicon) near4 (coat\$3 or deposit\$3 or film or layer or grow\$3 or \$4CVD) with (\$4CVD or (vapor adj deposit\$3)) same (selective\$3 or pattern\$3 or portion))) and ((deposit\$3 or apply\$3 or arrang\$3 or place or placed or placing or print\$3) near4 (liquid or solution or precursor or \$10silane) near4 (substrate or base or crucible or evaporator or source or vaporizer or vaporizer) with (evaporat\$3 or vaporize))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:28
38	41	((deposit\$3 or apply\$3 or arrang\$3 or place or placed or placing or print\$3) near4 (liquid or solution or precursor or \$10silane) near4 (substrate or base or crucible or evaporator or source or vaporizer or vaporizer) with (evaporat\$3 or vaporize) with (pattern\$3 or selective\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/16 10:29